

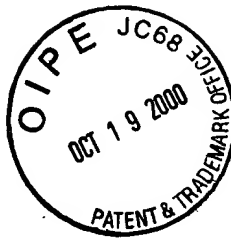
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Koji NOZAKI et al

Serial No.: 09/015,287

Filed: January 29, 1998



10/20  
Group Art Unit: 1752

Examiner: J. Chu

For: POLYMER COMPOUND FOR A CHEMICAL AMPLIFICATION RESIST AND A FABRICATION PROCESS OF A SEMICONDUCTOR DEVICE USING SUCH A CHEMICAL AMPLIFICATION RESIST

**REQUEST FOR STATUS**

Director of Patents and Trademarks  
Washington, D.C. 20231  
Sir:

Date: October 19, 2000

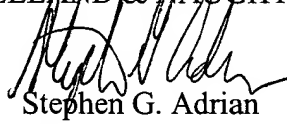
The undersigned attorney requests the status of the above-identified application.

A Patent Office Communication was mailed on April 10, 2000, indicating a six month suspension. To date no further action has been received.

In the event any fees are required in connection with this paper, please charge Deposit Account No. 01-2340.

Respectfully submitted,

ARMSTRONG, WESTERMAN, HATTORI,  
MCLELAND & NAUGHTON

  
Stephen G. Adrian  
Attorney for Applicant  
Reg. No. 32,878

Atty. Docket No. 980055  
1725 K Street, N.W., Suite 1000  
Washington, DC 20006  
Tel: (202) 659-2930  
Fax: (202) 887-0357  
SGA/arf

RECEIVED  
OCT 20 2000  
TC 1700 MAIL ROOM